## PATENT ABSTRACTS OF JAPAN

(11) Publication number: 2002357541 A

(43) Date of publication of application: 13.12.02

(51) Int. CI

G01N 21/27

G01M 11/00

G01N 21/94

G03G 21/00

G03G 21/16

(21) Application number: 2001164206

(71) Applicant:

**RICOH CO LTD** 

(22) Date of filing: 31.05.01

(72) Inventor:

MIYAUCHI TADANAO .

## (54) CONTAMINATION MONITOR FOR IMAGE FORMING APPARATUS

## (57) Abstract:

PROBLEM TO BE SOLVED: To provide a contamination monitor for an image forming apparatus capable of obtaining information to monitor a contaminating state of a component for forming an image and to clarify a type, a generation source and a generating state of a contaminant.

SOLUTION: The contamination monitor for the image forming apparatus comprises a high refractive index material 2 which has a large refractive index and which is transparent in an infrared region, an infrared ray source 1, a detector 3 and a reflecting mirror 4. The infrared ray IR is passing through the material 2 provided in the image forming apparatus while repeating total reflecting.

COPYRIGHT: (C)2003,JPO

